

JPM



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Kam-Leung, et al.

Serial No.: 10/627,753

Group Art Unit: 2823

Filed: July 28, 2003

Examiner: Brook Kebede

For: METHOD FOR SLOWING DOWN DOPANT-ENHANCED DIFFUSION
SUBSTRATES AND DEVICES FABRICATED THEREFROM

Honorable Commissioner for Patents
Alexandria, VA 22313-1450

SUBMISSION OF CORRECTED FORM 1449

Sir:

Submitted herewith is a corrected Form 1449. The Information Disclosure Statement filed December 8, 2004 included a minor typographical in the form PTO-1449.

That is, the form PTO-1449 cited U.S. Patent Application Publication No. 2003/009640 A1. The correct U.S. Patent Application Publication No. should read --“2003/009640 A1”--, which Publication was the one submitted. Applicants have attached a corrected form PTO-1449, correcting the above-identified typographical error.

Please note that the attached form PTO-1449 is not a new submission. The attached form PTO-1449 is merely a corrected form PTO-1449.

Acknowledgment of receipt is respectfully requested.

Respectfully submitted,

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Date: November 2, 2005

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INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)
YOR920030077US1Application Number
10/627,753Applicant(s)
Kam-Leung, et al.Filing Date
July 28, 2003Group Art Unit
2823

NOV 02 2005

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		US 2003/0096490 A1	5/22/03	John Borland, et al.			
		6,518,150 B1	02/11/03	Matsumoto			
		6,069,062	05/30/00	Downey			
		6,180,476 B1	01/30/01	Yu			
		6,380,053 B1	04/30/02	Komatsu			
		6,426,278 B1	07/30/02	Nowak, et al.			
		6,087,209	07/11/00	Yeap, et al.			
		6,410,393 B1	06/25/02	Hao, et al.			

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	WO 97/42652	11/13/97	PCT				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Article by T. H. Huang, et al.: "Influence of Fluorine Preamorphization on the Diffusion and Activation of Low-Energy Implanted Boron During Rapid Thermal Annealing", Applied Physics Letters, American Institute of Physics, NY, US Vol. 65, No. 14, October 3, 1994, pp. 1829-1831.
		Article by S. Saito, et al.: "Defect Reduction by MeV ion Implantation for Shallow Junction Formation, Applied Physics Letters, American Institute by Physics, Vol. 63, No. 2, July 12, 1993, pp. 197-199.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) YOR920030077US1	Application Number 10/627,753
Applicant(s) Kam-Leung, et al.	
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